

Monday

7.30	60	Registration
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8.30		Start Monday Morning Sessions
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Opening Session

8.30	10	Opening
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Session 1: Keynote session: Industrial Trends

8.40	30	Keynote: Roadmap Challenges – There is More than Moore
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A. J. van Roosmalen

Philips Semiconductors, Eindhoven, the Netherlands

9.10	30	Keynote: Opportunities and Challenges for Telecommunications Technology
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J. Rantala

Nokia Research Center, Helsinki, Finland

9.40	30	Keynote: Trends in automotive electronics
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H. Casier

AMI Semiconductor Belgium BVBA, Oudenaarde, Belgium

10.10	30	Keynote: Trends & Challenges in Microsystems Packaging
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M. K. Iyer

Microsystems, Modules & Components Lab, Institute of Microelectronics (IME), Singapore

10.40	30	Break
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Session 2: Keynote session: Technology Developments

11.10	30	Keynote: Nano-electronics in Biological Applications
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G. Borghs

IMEC, Leuven, Belgium

11.40	30	Keynote: Reliability Challenges and Recent Advances for Cu Interconnects
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Paul S. Ho^a, Ki-Don Lee^b, Sean Yoon^a, Guotao Wang^a

^aLaboratory for Interconnect and Packaging, University of Texas at Austin, USA

^bSilicon Technology Development, Texas Instruments, Inc., Dallas, USA

12.10	30	Keynote: From Macro-Cooling to Micro-Reliability
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M.R.D. Davies

Stokes Research Institute, University of Limerick, Ireland

12.40	100	Lunch
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14.20	Monday Afternoon Sessions
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Parallel sessions				
14.20-15.50	Session 3		Session 4	Session 5
	Virtual Thermal Mechanical Prototyping		Thermal Mechanical Behavior on Wafer Level	Dynamic Compact Thermal and Electro-Thermal Models

Session 3: Virtual Thermal Mechanical Prototyping		
14.20	30	Keynote: Modeling of Cure-Induced Warpage of Plastic IC Packages D.G. Yang ¹ , K.M.B. Jansen ¹ , L.J. Ernst ¹ , G.Q. Zhang ² , W.D. van Driel, H.J.L. Bressers ³ ¹ Delft University of Technology, The Netherlands, ² Philips-CFT, Eindhoven, The Netherlands ³ Philips Semiconductors, Nijmegen, The Netherlands
14.50	20	Thermo-Mechanical Stress Modelling of MOS Device with Electro-thermal Considerations P. Tounsi*, J.P. Fradin**, X. Chauffleur***, Ph. Dupuy**, J.M. Dorkel*, A. Marty*, A. Deram** *) LAAS/CNRS, Toulouse Cedex, France **) MOTOROLA Semiconducteurs SA, Toulouse Cedex, France ***) EPSILON Ingénierie, California, Labège Cedex, France
15.10	20	FEM-based Method to Determinate Mechanical Stress Evolution during Process Flow in Microelectronics – Application to Stress-Voiding S. Orain ¹ , J.C Barbe ² , X. Federspiel ¹ , P. Legallo ³ , H. Jaouen ⁴ ¹ PHILIPS semiconductors, Crolles cedex ; France ² CEA-DRT-LETI/DTS, Grenoble Cedex, France ³ CEA-DRT/DTEN, Grenoble Cedex, France ⁴ STMicroelectronics, Crolles Cedex, France
15.30	20	On Wire Failures in Micro-electronic Packages W.D. van Driel ¹ , J.H.J. Jansen, G.Q. Zhang ² , M.A.J. van Gils ² , R.B.R. van Silfhout ² , L.J. Ernst ³ ¹ ATO Innovation/Philips Semiconductors, Nijmegen, The Netherlands ² Center for Industrial Technology/Philips, Eindhoven, The Netherlands ³ Delft University of Technology, 2628 CD Delft, The Netherlands

Session 4: Thermal Mechanical Behavior on Wafer Level		
14.20	30	Keynote: A Finite Element Study of Process Induced Stress in the Transistor Channel: Effects of Silicide Contact and Gate Stack C.Torregiani ^{1,2} , J. Liu ³ , B.Vandeveld ¹ , D.Degryse ¹ , M.J.Van Dal ⁴ , A. Benedetti, A.Lauwers ¹ , K.Maex ^{1,2} . ¹ IMEC, Leuven, Belgium ² E.E. Dept. K.U.Leuven, Leuven, Belgium ³ E.E. Dept. Stanford University, Stanford, California, USA ⁴ Philips Research Leuven, Leuven, Belgium
14.50	20	Effect of Metal Layout Design on Passivation Crack Occurrence using both Experimental and Simulation Techniques R.B.R van Silfhout ¹ , W.D. van Driel ² , Y.Li ² , M.A.J. van Gils ¹ , J.H.J. Janssen ² , G.Q. Zhang ¹ , G. Tao ² , J. Bisschop ² , L.J. Ernst ³ ¹ Philips Centre for Industrial Technology, Eindhoven, The Netherlands ² Philips Semiconductors, ATO Innovation, Nijmegen, The Netherlands ³ Delft University of Technology, The Netherlands
15.10	20	Probability of Silicon Fracture in Molded Packages C. Bohm*, T. Hauck*, W. H. Müller**, A. Juritza *) Motorola GmbH, Schatzbogen 7, 81829 München **) Technische Universität Berlin, Einsteinufer 5, 10587 Berlin
15.30	20	Interfacial Sliding and Plasticity in Back-end Interconnect Structures of Microelectronic devices I. Dutta ¹ , D. Pan, C. Park ¹ , J. Vella ² ¹ Center for Materials Science and Engineering, Department of Mechanical Engineering, Naval Postgraduate School, Monterey, CA, USA ² Process and Materials Characterization Laboratory, Motorola, Tempe, AZ, USA

Session 5: Dynamic Compact Thermal and Electro-Thermal Models		
14.20	30	Keynote: Empirical Validation of Thermal Dynamics in a Silicon Microthruster: Influence of the Boundary Conditions <i>M. Salleras, I. García, J. Palacín, M. Puig, J. Samitier, S. Marco</i> <i>Sistemes d'Instrumentació i Comunicacions, Departament d'Electrònica, Universitat de Barcelona, Spain</i>
14.50	20	Compact Electro-thermal Models of Semiconductor Devices with Multiple Heat Sources <i>C. Bohm, T. Hauck, E.B. Rudnyi, J. G. Korvink</i> <i>Motorola, Germany IMTEK, University of Freiburg, Germany</i>
15.10	20	Electro-Thermal Transistor Models in the SSISS Electro-Thermal IC Simulator <i>V.Székel, A.Poppe, G.Hajas</i> <i>Budapest University of Technology and Economics, Hungary</i>

15.50	40	Break
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Parallel sessions				
16.30-18.00	Session 6		Session 7	Session 8
	Experimental and Numerical Interaction		Modeling and Designing of Advanced Packaging	Thermal Behavior Modeling and Characterization

Session 6: Experimental and Numerical Interaction		
16.30	30	Keynote: Computational Model Validation with Experimental Data from Temperature Cycling Tests of PBGA Assemblies for the Analysis of Board Level Solder Joint Reliability <i>R. Lee, D. Lau</i> <i>Electronic Packaging Laboratory, Department of Mechanical Engineering Hong Kong University of Science & Technology, Hong Kong</i>
17.00	20	PWB Warpage Analysis and Verification using an AP210 Standards-based Engineering Framework and Shadow Moiré <i>D. Zwemer¹, S. McCarron¹, A. Spradling¹, R. Peak², M. Bajaj², T. Thurman³, M. Dickerson⁴, L. Klein⁵, G. Liutkis⁵, K. Brady⁶, J. Messina⁶</i> ¹⁾ AkroMetrix LLC, USA ²⁾ Georgia Institute of Technology, USA ³⁾ Rockwell Collins, USA ⁴⁾ InterCAX LLC, USA ⁵⁾ LKSoft, USA ⁶⁾ NIST, USA
17.20	20	Novel Numerical and Experimental Analysis of Dynamic Responses under Board Level Drop Test <i>Tong Yan Tee^a, Jing-en Luan^a, Eric Pek^b, Chwee Teck Lim^b, Zhaowei Zhong^c</i> ^a STMicroelectronics, Singapore ^b National University of Singapore, ME Dept, Singapore. ^c Nanyang Technological University, School of MPE, Singapore.
17.40	20	Finite Element Modelling of Crack Detection Tests <i>S Ridout¹, M Dusek², C Bailey¹, C Hunt²</i> ¹⁾ Centre for Numerical Modelling and Process Analysis, University of Greenwich, Greenwich, UK ²⁾ NPL Materials Centre, National Physical Laboratory,, Teddington, UK

Session 7: Modeling and Designing of Advanced Packaging		
16.30	30	Keynote: Design, Fabrication and Comparison of Lead-Free/Eutectic Solder Joint Reliability of FlipChip Package <i>Chih-Tang Peng, Kuo-Ning Chiang, Terry Ku, Kenny Chang</i> <i>National Tsing Hua University, Taiwan</i>
17.00	20	Virtual Qualification of Moisture Induced Failures of Advanced Packages <i>M.A.J. van Gils¹, W.D. van Driel², G.Q. Zhang³, H.J.L. Bressers², R.B.R. van Silfhout¹, X.J. Fan⁴, J.H.J. Janssen²</i> ¹⁾ Philips Center for Industrial Technology, Eindhoven, The Netherlands ²⁾ ATO Innovation/Philips Semiconductors, Nijmegen, The Netherlands ³⁾ Technical University of Eindhoven, Eindhoven, The Netherlands ⁴⁾ Philips Research-USA, Briarcliff Manor, New York, USA
17.20	20	Finite Element Analysis of an Improved Wafer Level Package using Silicone Under Bump (SUB) Layers <i>M. Gonzalez¹, M. Vanden Bulcke¹, B. Vandeveld¹, E. Beyne¹, Y. Lee², B. Harkness², H. Meynen²</i> ¹⁾ IMEC, Leuven, Belgium ²⁾ Dow Corning Corporation
17.40	20	Crack and Delamination Risk Evaluation of Thin Silicon Applications based on Fracture Mechanics Approaches <i>J. Auersperg^{1,2}, D. Vogel¹, B. Michel¹</i> ¹⁾ Fraunhofer Institute for Reliability and Microintegration Berlin (IZM), Dept. Mechanical Reliability and Micro Materials, Berlin, Germany ²⁾ AMIC Angewandte Micro-Messtechnik GmbH, Berlin, Germany

Session 8: Thermal Behavior Modeling and Characterization		
16.30	30	Keynote: Numerical Simulation and Experimental Verification of the Thermal Contact Properties of the Polymers Bonds <i>T. Falat, A. Wymyslawski, K. Friedel, J. Felba</i> <i>Wroclaw University of Technology, Poland</i>
17.00	20	Experiments on Behaviour of Power Silicon PN Junctions under Reverse Bias Voltage at High Temperature <i>V.V.N. Obreja¹, C. Codreanu¹, K. Nuttall², O. Buiu²</i> ¹⁾ National R&D Institute for Microtechnology, Romania ²⁾ Liverpool University, UK
17.20	20	Parameter Calibration on Post-ion-implantation Dopant Diffusions <i>J. Fu, W. Crans², W.J. Eijssenga²</i> ¹⁾ X-FAB Semiconductor Foundries, Erfurt, Germany ²⁾ TU Delft, ITS-Faculty/DIMES, Electronic Components, Technology and Materials (ECTM)-Lab, Delft, The Netherlands

18.00		End of 1 st day Technical Sessions
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Tuesday

8.30 Start Tuesday Morning Sessions

Parallel sessions			
8.30-10.20	Session 9		Session 10
	Advanced Numerical Simulation Methodologies		Small Scale Thermal and Fluid Aspects in Microsystems

Session 9: Advanced Numerical Simulation Methodologies			
8.30	30	Keynote: Automated FEM Mesh Optimization for Nonlinear Problems Based on Error Estimation S. Rzepka <i>Infinion Technologies SC 300 Dresden, MDC RM, Dresden, Germany</i>	
9.00	20	Advanced Numerical Prototyping Methods in Modern Engineering Applications W.D. van Driel¹, J. van de Peer³, N. Tzannetakis³, A. Wymyslawski⁴, G.Q. Zhang² ¹⁾ ATO Innovation/Philips Semiconductors, Nijmegen, The Netherlands ²⁾ Center for Industrial Technology/Philips, Eindhoven, The Netherlands ³⁾ Noesis, Leuven, Belgium ⁴⁾ Wroclaw University of Technology, Wroclaw, Poland	
9.20	20	Reliability-Based Design Optimization for Land Grid Array Solder Joints Under Thermo-Mechanical Load Zhenxue Han¹, Bo Wang¹, Leon Xu², Tommi Reinikainen², Ren Wei² ¹⁾ University of Texas at Arlington, USA ²⁾ Nokia, USA	
9.40	20	Finite Element Analysis of Ultra Thin BGA Package: First and Second Level Reliability P. Limaye¹, B. Vandeveld¹, H. deVries², D. Degryse¹, K. Slob², C. van Veen², R. Labie¹ ¹⁾ IMEC, Leuven, Belgium ²⁾ Philips CFT (Eindhoven), The Netherlands	
10.00	20	Application of Simulation-based Decision Making in Product Development of an RF Module M. Lindgren^{1,2}, I. Belov², M. Törnqvall¹, P. Leisner^{2,3}, ¹⁾ Kitron Development AB, Jönköping, Sweden ²⁾ School of Engineering, Jönköping university, Sweden ³⁾ Acreo AB, Jönköping, Sweden	

Session 10: Small Scale Thermal and Fluid Aspects in Microsystems		
8.30	30	Keynote: Data on the Velocity Slip and Temperature Jump Coefficients <i>F. Sharipov</i> <i>Universidade Federal do Paraná, Brazil</i>
9.00	20	Shear Driven Micro-Flows of Gaseous Mixtures <i>D. Valougeorgis, S. Naris</i> <i>University of Thessaly, Greece</i>
9.20	20	Effect of Slip on Transient Liquid Flow Development in Micro-Channels <i>M.N. Sabry¹, A.R. Abdel-Rahim², M.H. Mansour²</i> ¹⁾ <i>Université Française d’Egypte, Egypt</i> ²⁾ <i>Mansoura University, Egypt</i>
9.40	20	Model Order Reduction of 3D Electro-Thermal Model for a Novel Micromachined Hotplate Gas Sensor <i>T. Bechtold¹, J. Hildenbrand¹, J. G. Korvink¹, J. Wollenstein²</i> ¹⁾ <i>IMTEK, University of Freiburg, Germany</i> ²⁾ <i>Institute for Physical Measurement Techniques, Germany</i>
10.00	20	Non-contact Thermal Conductivity Measurements of P-doped and N-doped Gold Covered Natural and Isotopically-Pure Silicon and their Oxides <i>M. G. Burzo, P. L. Komarov, P. E. Raad</i> <i>Southern Methodist University, Dallas</i>

10.20	20	Break
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Parallel poster sessions				
10.40-11.30	Session 11		Session 12	Session 13
	Modeling in Micro Technology		Designing for Reliability	Material Characterization and Modeling

Session 11: Poster session: Modeling in Micro Technology		
10.40	50	Design and analysis of novel glass WLCSP structure <i>Chang-Ann Yuan, Cheng Nan Han, Kou-Ning Chiang</i> <i>Department of Power Mechanical Engineering, National Tsing Hua University, HsinChu, Taiwan</i>
		State of the Art in Prediction of Mechanical Behaviour of Microsystems <i>M. Lishchynska, N. Cordero, O. Slattery</i> <i>NMRC, Lee Maltings, Prospect Row, Cork, Ireland</i>
		Behavioral VHDL-AMS Modeling of Nuclear Magnetic Resonance Sensor <i>S. Megherbi¹, J.-C. Ginefri², L. Darrasse², G. Raynaud¹, J.-F. Pône¹</i> ¹⁾ <i>Institut d’Electronique Fondamentale, France</i> ²⁾ <i>Unité de Recherche en Résonance Magnétique Médicale, University of Paris-Sud, France</i>
		3D-FEM Modelling of an Electro-Optical Micro-Shutter <i>P. Roux¹, E. Woïrgard¹, M. Pizzi²</i> ¹⁾ <i>IXL Laboratory, University of Bordeaux, Talence, France</i> ²⁾ <i>Centro Ricerche Fiat (CRF), Orbassano, Italia</i>
		Novel 2D Micronib Ionization Sources for Nano Electrospray-Mass Spectrometry (ESI-MS) <i>S. Le Gac¹, S. Arscott^{1,2}, C. Rolando¹</i> ¹⁾ <i>USTL, UPRESA CNRS 8009, Villeneuve d’Ascq Cedex, France</i> ²⁾ <i>IEMN, UMR CNRS 8520, Villeneuve d’Ascq Cedex, France.</i>

Session 12: Poster session: Designing for Reliability	
10.40	50
	A Study of Cyclic Bending Reliability of Bare-die-type Chip-scale Packages <i>Yi-Shao Lai¹, Tong Hong Wang, Han-Hui Tsai, Jenq-Dah Wu</i> <i>Stress Characterization Laboratory, Advanced Semiconductor Engineering, Inc., Nantze, Kaohsiung, Taiwan</i>
	Three-Dimensional Stress Analysis of Ink Marking Process <i>Chang-Lin Yeh¹, Yi-Hsien Lin, Yi-Shao Lai, Hsiao-Chuang Chang, Jenq-Dah Wu</i> <i>Advanced Semiconductor Engineering, Inc., Nantze, Kaohsiung, Taiwan</i>
	Microprocessor Packaging Strategy: Reliability of various Flip Chip BGA Packages on different Printed Circuit Boards <i>A. Guillaume¹, C. Munier¹, C. Allégret², M. Michaud²</i> ¹⁾ EADS CCR, Service DCR/EP/EO, SURESNES Cedex, France ²⁾ MBDA, Vélizy Villacoublay, France
	Mechanism-Based Delamination Prediction During Reflow with Moisture Preconditioning <i>X.J. Fan⁴, L.J. Ernst¹, G.Q.Zhang², W. van Driel³</i> ¹⁾ Delft University of Technology, Delft, The Netherlands ²⁾ Philips Cft, Eindhoven ³⁾ ATO Innovation/Philips Semiconductors, Nijmegen, The Netherlands ⁴⁾ Philips Research USA, New York, USA
	Microstructural Stability and Failure Modes in Eutectic Sn-Ag-Cu Solder <i>M. A. Matin, W. P. Vellinga, and M. G. D. Geers</i> <i>Division of Materials Technology, Department of Mechanical Engineering, Eindhoven University of Technology, Eindhoven, The Netherlands</i>
	Analysis of Thermal-Moisture Induced Failure of Pb-free Soldered IC Packages in SMT Reflow Soldering Process <i>Ning Sun¹, Dachuan Lin¹, Daoguo Yang^{1,2}</i> ¹⁾ Guilin University of Electronic Technology, Guilin, China ²⁾ Delft University of Technology, The Netherlands

Session 13: Poster session: Material Characterization and Modeling		
10.40	50	Rupture Test on Polysilicon Films Through Electrostatic Actuation F. Cacchione¹, B. De Masi², A. Corigliano¹, M. Ferrera² ¹⁾ Department of Structural Engineering, Politecnico di Milano, Milano, Italy ²⁾ MEMS Business Unit, STMicroelectronics, Cornaredo, (Milano), Italy
		Evaluation of the Primary and Secondary Creep of SnPb Solder Joint Using a Modified Grooved-lap Test Specimen. S. Déplanque¹, W. Nüchter¹, B. Wunderle², H. Walter², B. Michel² ¹⁾ Robert BOSCH GmbH, Stuttgart, Germany ²⁾ IZM Fraunhofer Institut Zuverlässigkeit und Mikrointegration, Berlin, Germany
		Numerical Simulation and Experimental Verification of the Piezoresistivity Phenomenon for the Printed Thick-Film Piezoresistors A. Wymysłowski¹, M. Santo – Zarnik^{2,3}, K. Friedel¹, D. Belavic^{2,3} ¹⁾ Wrocław University of Technology, Wrocław, Poland ²⁾ Jožef Stefan Institute, Ljubljana, Slovenia ³⁾ HIPOT-R&D, Šentjernej, Slovenia
		Void Formation in a Copper-Via-Structure Depending on the Stress Free Temperature and Metallization Geometry K. Weide¹, D. Dalleau¹, Y. Danto², H. Fremont² ¹⁾ Laboratorium für Informationstechnologie, University of Hannover, Germany ²⁾ IXL, Université Bordeaux I, Talence, France
		Mechanical Characterisation of SiLK by Nanoindentation and Substrate Curvature Techniques V. Gonda¹, K.M.B. Jansen¹, L.J. Ernst¹, Jaap den Toonder¹, G.Q. Zhang³ ¹⁾ Delft University of Technology, Delft, The Netherlands ²⁾ Philips Research Laboratories, Eindhoven, The Netherlands ³⁾ Center for Industrial Technology/Philips, Eindhoven, The Netherlands
		Cantilever Microbeams: Modelling of the Dynamical Behaviour and Material Characterization R. Yahiaoui, A. Bosseboeuf Institut d'Electronique fondamentale, University of Paris-sud Orsay, Orsay, France
		A Novel Tool for Cure Dependent Viscoelastic Characterization of Packaging Polymers C. van 't Hof¹, L.J. Ernst¹, K.M.B. Jansen¹, D.G. Yang¹, H.J.L. Bressers², G.Q. Zhang³ ¹⁾ Delft University of Technology, Delft, The Netherlands ²⁾ Philips Semiconductors, Nijmegen, The Netherlands ³⁾ Center for Industrial Technology/Philips, Eindhoven, The Netherlands

Parallel sessions		
11.30-12.40	Session 14	Session 15
	Modeling of MEMS and Optical Devices	Simulation-Based Thermal Design Strategies

Session 14: Modeling of MEMS and Optical Devices		
11.30	30	Keynote: Hardware Description Language Modeling of an Electrostatically Actuated bi-axial Micromirror <i>F. Parrain¹, S. Megherbi¹, G. Raynaud¹, H. Mathias¹, J. Gilles¹, A. Bosseboeuf¹, G. Schröpfer², P. Cusin³, N. Faure³</i> ¹⁾ Institute d'Electronic Fondamentale UMR8622 – Université Paris-Sud, Orsay Cedex, France ²⁾ Coventor Sarl, Villebon, France ³⁾ Colibris SA, Neuchâtel, Switzerland
12.00	20	Polymer Waveguide and VCSEL Array Multi-Physics Modelling for OECB Based Optical Backplanes <i>D. Gwyer¹, P. Missebrook^{2,3}, C. Bailey¹, P.P. Conway³, K. Williams³</i> ¹⁾ Centre for Numerical Modelling and Process Analysis, University of Greenwich, London, UK ²⁾ Celista, Stoke-on-Trent, UK ³⁾ Interconnection Group, Loughborough University, Loughborough, UK
12.20	20	Determination of Residual Stress in Glass Frit Bonded MEMS by Finite Element Analysis <i>M. Ebert, J. Bagdahn</i> <i>Fraunhofer- Institute for Mechanics of Materials Halle, Germany</i>

Session 15: Simulation-Based Thermal Design Strategies		
11.30	30	Keynote: A Computer-Architecture Approach to Thermal Management in Computer Systems: Opportunities and Challenges <i>K. Skadron, M.R. Stan, W. Huang, Zhijian Lu, K. Sankaranarayanan, J. Lach</i> <i>University of Virginia, USA</i>
12.00	20	Tri-dimensional reduced-order Thermal Model of Stacked Electronic Structures <i>V. Feuillet¹, V. Gatto¹, Y. Scudeller², Y. Jarny¹</i> ¹⁾ Laboratoire de Thermocinétique ²⁾ Laboratoire de Génie des Matériaux <i>Ecole polytechnique de l'université de Nantes, Nantes, France</i>
12.20	20	Thermal Modeling for Power MOSFETs in DC-DC Applications <i>Y. Bulut, K. Pandya</i> <i>Vishay Siliconix, USA</i>

12.40	100	Lunch
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14.20	Start Tuesday Afternoon Sessions	
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14.20		Start Tuesday Afternoon Sessions
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Parallel sessions		
14.20-16.10	Session 16	Session 17
	Solder Reliability Behavior	CFD and FE Modelling of Thermal Performance

Session 16: Solder Reliability Behavior		
14.20	30	Keynote: Reliability of SnPb and Pb-Free Flip-Chips under Different Test Conditions M. Spraul¹, W. Nüchter¹, A. Möller¹, B. Wunderle², B. Michel² ¹⁾ Robert Bosch GmbH, Germany ²⁾ Fraunhofer-IZM, Berlin, Germany
14.50	20	Microstructural and Mechanical Characterization of 95.5Sn-4Ag-0.5Cu Solder Balls by Nano-Indentation M. Erinc¹, P. Schreurs¹, G.Q. Zhang¹, W. D. van Driel², M. Geers¹ ¹⁾ Technical University of Eindhoven, Eindhoven, The Netherlands ²⁾ ATO Innovation/Philips Semiconductors, 6534 AE Nijmegen, The Netherlands
15.10	20	Modeling Stress Strain Curves For Lead Free 95.5Sn-3.8Ag-0.7Cu Solder J.H.L. Pang, B.S. Xiong and T.H. Low Nanyang Technological University, School of Mechanical and Production Engineering, Singapore
15.30	20	Effect of Different Temperature Cycle Profiles on the Crack Propagation and Microstructural Evolution of Real Lead Free Joints of Different Electronic Components C. Andersson^{1,2}, D. Andersson^{1,3}, P-E Tegehall^{1,3}, Johan Liu^{1,2,3} ¹⁾ Swedish Microsystem Integration Technology (SMIT) Center ²⁾ Division of Electronics Production, Chalmers University of Technology, Mölndal, Sweden ³⁾ IVF Industrial Research and Development Corporation, Sweden
15.50	20	A Review of Creep Fatigue Failure Models in Solder Material - Simplified Use of a Continuous Damage Mechanical Approach G. Massiot, C. Munier EADS Corporate Research Center, Suresnes cedex, France

Session 17: CFD and FE Modeling of Thermal Performance		
14.20	30	Keynote: Thermal and Flow Analysis of SiC-Based Gas Sensors for Automotive Applications I. Below¹, P. Leisner¹, H. Wingbran², A.L. Spetz², H. Sundgren², B. Thuner², H. Svenningstorp³, P. Leisner⁴ ¹⁾ Jönköping University, Sweden ²⁾ Linköping University, Sweden ³⁾ Volvo Technology Corporation, Sweden ⁴⁾ Acreo, Sweden
14.50	20	Low Reynolds Number Turbulence Models for Accurate Thermal Simulations of Electronic Components K Dhinsa, C Bailey, K Pericleous University of Greenwich, UK
15.10	20	Thermal Testing of a 3-Die Stacked Chip Scale Package Including Evaluation of Simplified and Complex Package Geometry Finite Element Models B.A. Zahn ChipPAC, USA
15.30	20	Thermal Analysis of QFN Packages Using Finite Element Method C.L. Chang, Y.Y. Hsieh National Yunlin University of Science and Technology, Taiwan
15.50	20	Experimental Study on Visualization of a Longitudinal Heat Sink with Top-mounted Fan by Particle Tracking J.H. Jang Kuang-Wu Institute of Technology, Taiwan

16.10	20	Break
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Special Exhibitor session		
16.30		

18.00		End of 2 nd day Technical Sessions
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Wednesday

8.30 Start Wednesday Morning Sessions

Session 18: **Keynote session: Micro- to Macro-Scale Thermal Design Challenges in Microelectronics**

8.30	30	Keynote: Modeling Heat Transfer and Liquid Flow in Micro-Channels <i>M.N. Sabry¹, B.O. Djebdjian², S.H. Saleh², M.M. Mahgoub²</i> ¹) Université Française d’Egypte, Egypt ²) Mansoura University, Egypt
9.00	30	Keynote: Cooling Problems and Thermal Issues in High Power Electronics: a Multi-Faceted Design Approach <i>M. Behnia¹, L. Maguire², G. Morrison²</i> ¹) The University of Sidney, Australia ²) University of New South Wales, Australia
9.30	30	Keynote: Design Challenges for High-Performance Heat Sinks used in Microelectronic Equipment: Evolution and Future Requirements <i>P. Rodgers¹, V. Eveloy²</i> ¹) CALCE Electronic Products and Systems Center, University of Maryland, USA ²) Electronics Thermal Management, Ltd., Ireland

10.00 40 Break

Parallel sessions

10.40-12.30	Session 19	Session 20
	Solder Fatigue	Characterization and Modeling of Polymer behavior

Session 19: Solder Fatigue

10.40	30	Keynote: A Mechanics-Based Strain Gage Methodology for Direct Solder Joint Reliability Assessment <i>L.L. Mercado, S. Girouard, G. Hsieh</i> <i>Intel, Chandler, USA</i>
11.10	20	Microstructural Behaviour of Solder Alloys <i>R.L.J.M. Ubachs, P.J.G. Schreurs, M.G.D. Geers</i> <i>Eindhoven University of Technology, Departement of Materials Technology, Eindhoven, The Netherlands.</i>
11.30	20	Flip Chip Solder Joint Fatigue Analysis Using 2D and 3D FE Models <i>A. Yeo¹, C. Lee¹, J. H.L. Pang²</i> ¹) Infineon Technologies Asia Pacific Pte Ltd, Assembly & Interconnect Technology, Singapore ²) *School of Mechanical and Production Engineering, Nanyang Technological University, Singapore
11.50	20	Thermal Fatigue Modelling for SnAgCu and SnPb Solder Joints <i>R. Dudek, H. Walter, R. Doering, B. Michel</i> <i>Fraunhofer IZM, Berlin, Germany</i>
12.10	20	Thermal Cycling Reliability of SnAgCu and SnPb Solder Joints: A Comparison for Several IC-Packages <i>B. Vandevelde, M. Gonzalez, P. Limaye, P. Ratchev, E. Beyne</i> <i>IMEC, Leuven, Belgium</i>

Session 20: Characterization and Modeling of Polymer behavior		
10.40	30	Keynote: Molecular Modeling Studies of IC Barrier Concerns. <i>N. Iwamoto,</i> <i>Honeywell Specialty Materials, Morristown, USA</i>
11.10	20	Molecular Simulation of Cu-SAM Adhesion Force <i>H. Fan, C.K. Wong, M.M.F. Yuen</i> <i>Department of Mechanical Engineering, Hong Kong University of Science and Technology, Kowloon, Hong Kong</i>
11.30	20	Cure, Temperature and Time dependent Constitutive Modeling of Moulding Compounds <i>K.M.B. Jansen¹, L. Wang¹, D.G. Yang¹, C. van 't Hof¹, L.J. Ernst¹, H.J.L. Bressers², G.Q. Zhang³</i> ¹ <i>Delft University of Technology, Delft, The Netherlands</i> ² <i>Philips Semiconductors, Nijmegen, The Netherlands</i> ³ <i>Philips CFT, Eindhoven, The Netherlands</i>
11.50	20	Simulation of No-Flow Underfill Process for Flip-Chip Assembly <i>A. Kolbeck¹, T. Hauck¹, J. Jendry², O. Hahn², S. Lang³</i> ¹ <i>Motorola GmbH, Deutschland</i> ² <i>LWF, Universität Paderborn, Deutschland</i> ³ <i>CADFEM GmbH, Grafing, Germany</i>
12.10	20	Mechanical Properties of Molding Compounds (MCs) under Different Moisture Conditions and in a Wide Temperature Range <i>W.H. Zhu, S. L. Gan, C.L. Toh</i> <i>Assembly and Interconnect Technologies, Infineon Technologies Asia Pacific Pte Ltd, Singapore</i>

12.30	90	Lunch
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14.00		Start Wednesday Afternoon Sessions
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Session 21: Keynote session: New Developments in Microelectronics Reliability		
14.00	30	Keynote: Challenges of Thermomechanical Design and Modeling of Ultra Fine-Pitch Wafer Level Packages <i>A. A. O. Tay</i> <i>Department of Mechanical Engineering, Nano/Microsystems Integration Laboratory, National University of Singapore, Singapore</i>
14.30	30	Keynote: Topography and Deformation Measurement under Thermomechanical Stress <i>R. Fayolle, J. Lecomte</i> <i>Insidix, Seyssins, France</i>
15.00	30	Keynote: Reliability of Interfaces for Lead-Free Solder Bumps <i>R.L.H. Shih¹, D.Y.K. Lau², R.W.M. Kwok^{2*}, M. Li³, M.K.W. Sun⁴</i> ¹ <i>Department of Chemistry, The Chinese University of Hong Kong, Shatin, N.T., Hong Kong</i> ² <i>Rohm and Haas Electronic Materials Asia Limited, 15 On Lok Mun Street, Fanling, N.T., Hong Kong</i> ³ <i>Department of Electronic Engineering, The Chinese University of Hong Kong, Shatin, N.T., Hong Kong</i> ⁴ <i>Department of Physics, The Chinese University of Hong Kong, Shatin, N.T., Hong Kong</i>
15.30	30	Keynote: From Chemical Building Blocks of Polymers to Microelectronics Reliability <i>H.J.L. Bressers², W.D. van Driel³, K.M.B. Jansen¹, L.J. Ernst¹ and G.Q. Zhang³</i> ¹ <i>Delft University of Technology, Delft, The Netherlands</i> ² <i>Philips Semiconductors, Nijmegen, The Netherlands</i> ³ <i>Philips CFT, Eindhoven, The Netherlands</i>

16.00	End of Conference
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